

DEMS™

Diethoxymethylsilane

Product Description

Schumacher's DEMS is a liquid precursor used for the chemical vapor deposition of high-quality low dielectric constant precursors.

Air Products: Global Supplier of CVD Low-K Dielectric Precursors

Air Products offers a comprehensive low-k package, including a variety of high-purity electronic specialty gases, its Schumacher unit's low-k chemical product line, delivery equipment and MEGASYS® on-site management services to maximize productivity and speed the development of new systems.

The company's portfolio of interlayer dielectric (ILD) precursors products includes SiH₄, SiF₄, 3MS™ and chlorosilane (TCS, STC, DCS).

Air Products' Schumacher unit offers several proven ILD products, including TEOS, ZTOMCATS™, Z4MS™, DMDMOS CVD low-k precursors, PDEMS ILD Precursor and our MesoELK™ SiO₂ precursor.

In addition, Air Products offers a full line of gas and chemical delivery equipment providing a high degree of safety and effective use of its low-k products. Offerings include the company's CHEMGUARD™ and GASGUARD® gas cabinets.

Table 1

Physical Characteristics

Formula	C ₅ H ₁₄ O ₂ Si
Molecular Weight	134.3
Boiling Point	-95° C
Freezing Point	< 0° C
Flash Point	10° C
Specific Gravity	0.831 (H ₂ O=1)
Vapor Density	7.5

For More Information

This datasheet has provided only a brief overview of Air Products' wide range of low-k solutions. If you would like more information, please contact:

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